

**Supplementary Figures:**

- Figure 1S:** FT-IR spectra of CMK-3 materials treated with APS at different oxidation (wavenumber range 400 to 4000  $\text{cm}^{-1}$ ): (a) CMK-3-0h, (b) CMK-3-2h, (c) CMK-3-6h, (d) CMK-3-12h, (e) CMK-3-24h, and (f) CMK-3-48h.
- Figure 2S:** Effect of the oxidation treatment time on the textural parameters of CMK-3 materials: (●) pore diameter (■) specific surface area, and (▲) specific pore volume.
- Figure 3S:** Nitrogen adsorption-desorption isotherms of CMK-3 materials treated with APS at different reaction time (open symbols – desorption; closed symbols – adsorption): (●) CMK-3-2h, (■) CMK-3-12h, (▲) CMK-3-24h, and (▼) CMK-3-48h.
- Figure 4S:** Powder XRD patterns of CMK-3 materials treated with different concentration of APS: (a) CMK-3-0.26M, (b) CMK-3-0.5M, (c) CMK-3-1.0M, and (d) CMK-3-1.75M.
- Figure 5S:** FT-IR spectra of CMK-3 materials treated with different concentration of APS (wavenumber range 400 to 4000  $\text{cm}^{-1}$ ): (a) CMK-3-0M, (b) CMK-3-0.26M, (c) CMK-3-0.5M, (d) CMK-3-1.0M, and (e) CMK-3-1.75M.

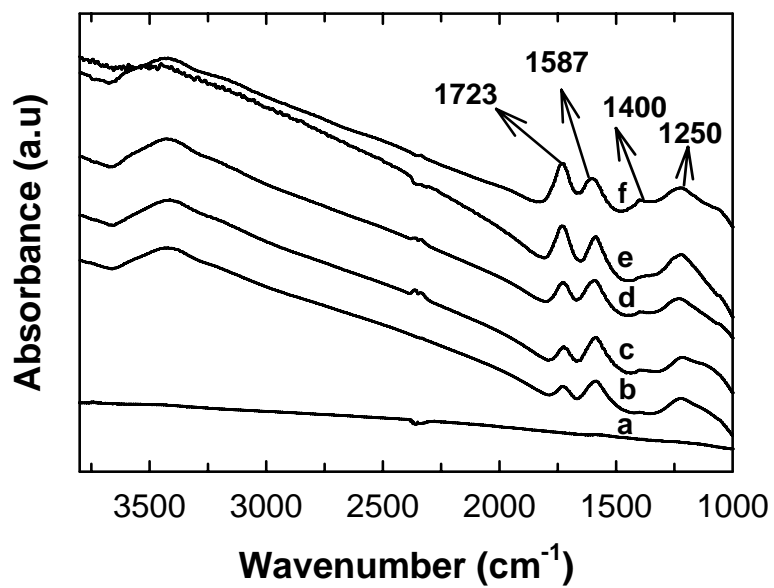


Figure 1S

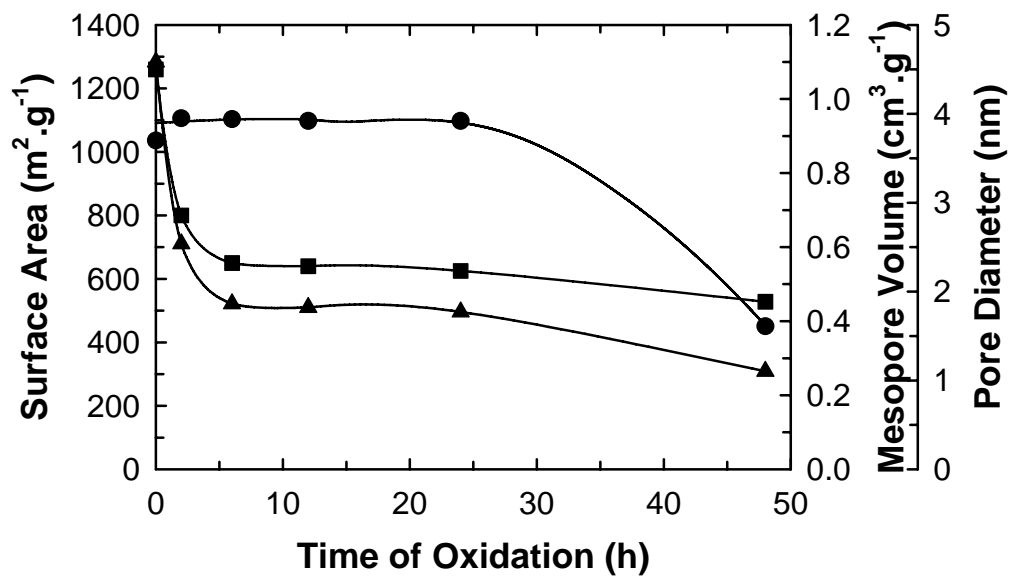


Figure 2S

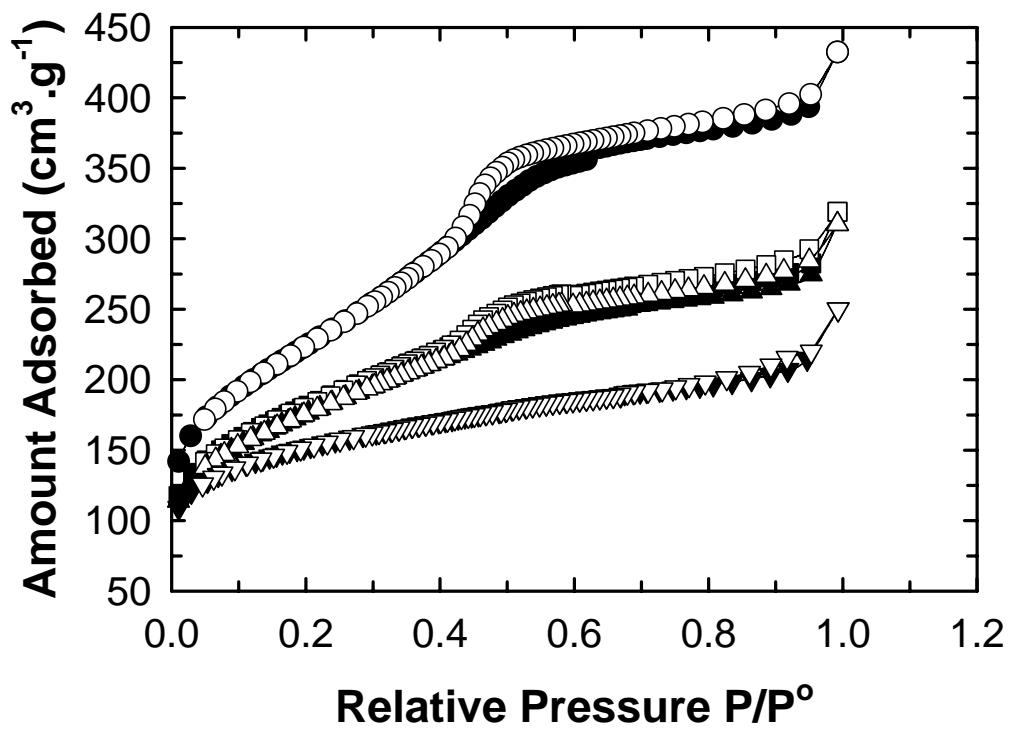


Figure 3S

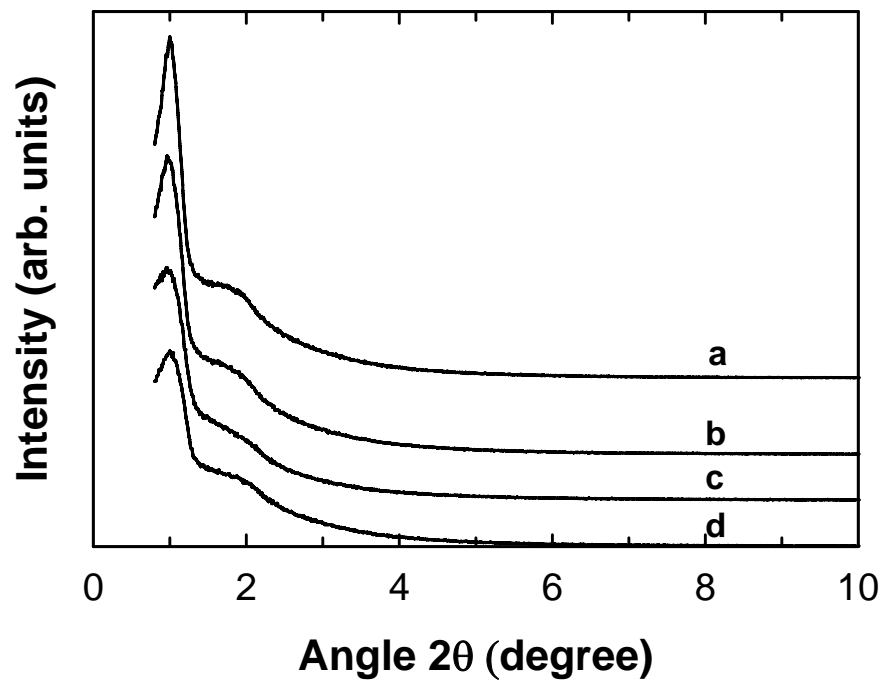


Figure 4S

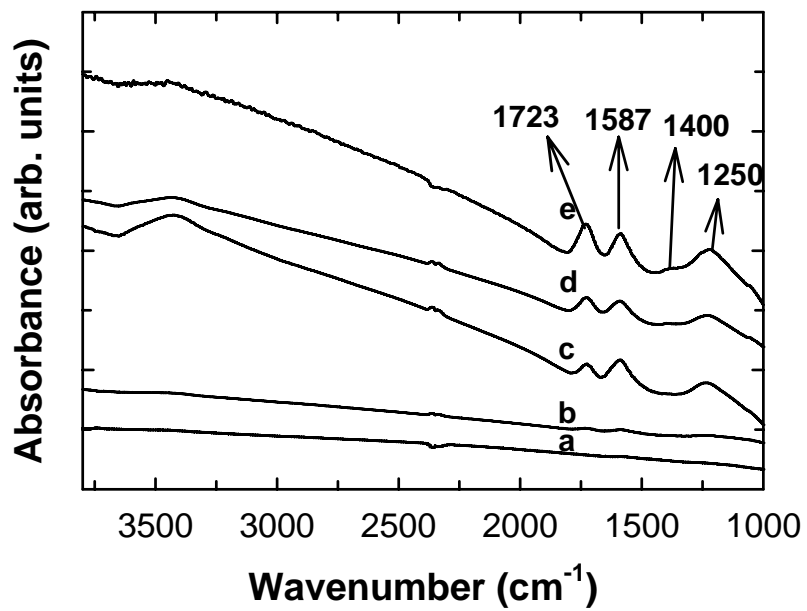


Figure S5